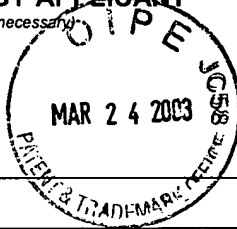


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Application Number	09/945512
Filing Date	August 30, 2001
First Named Inventor	Forbes, Leonard
Group Art Unit	2812
Examiner Name	Booth, Richard

Sheet 1 of 3

Attorney Docket No: 1303.027US1

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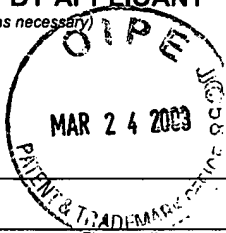
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*Richard A. Booth*

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Attorney Docket No: 1303.027US1

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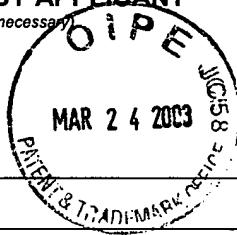
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Application Number	09/945512
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Group Art Unit	2812
Examiner Name	Booth, Richard

Sheet 3 of 3

Attorney Docket No: 1303.027US1

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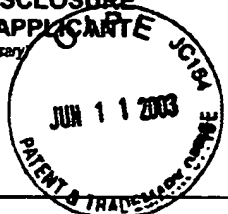
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